



Session Title:	[ThF1] Nano Thin Film Deposition VI
Session Date:	November 14 (Thu.), 2024
Session Time:	09:00-10:30
Session Room:	Room F (Ballroom, 5F, Grand Josun Busan)
Session Chair:	Prof. Se-Hun Kwon (Pusan Nat'l Univ., Korea)

[ThF1-1] [Invited] 09:00-09:30

Enhancing ALD Growth Characteristics through Surface Reaction Control

Changbong Yeon, Kok Chew Tan, Jung Hun Lim, Young-Soo Park, and Jaesun Jung (Soulbrain Co., Ltd., Korea)

[ThF1-2] 09:30-09:50

Thermal Atomic Layer Deposition of Aluminum Nitride Films Using Tris(dimethylamido)aluminum and Ammonia

Okhyeon Kim, Yerim Choi, Jian Heo, Changgyu Kim, Hye-Lee Kim, and Won-Jun Lee (Sejong Univ., Korea)

[ThF1-3] 09:50-10:10

Effect of Tunable Sub-Source and Sub-Drain Device Behavior in Four-Terminal Operation Using Metal-Capping Thin-Film Transistors

Ji Ye Lee (Korea Univ., Korea), Hyeon Dong Kim, Tae Ho Kim, Sang Ji Kim, Byeong-Kwon Ju (Korea Univ., Korea), and Sang Yeol Lee (Gachon Univ., Korea)

[ThF1-4] 10:10-10:30

Ultrathin Metal Films with Low Resistivity via Atomic Layer Deposition: Process Pressure Effect on Initial Growth Behavior of Ru Films

Na-Gyeong Kang, Min-Ji Ha, and Ji-Hoon Ahn (Hanyang Univ., Korea)